## 10696782\_CLS.txt Most Frequently Occurring Classifications of Patents Returned From A Search of 10696782 on February 15, 2005

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Original Classifications

8 250/492.21

2 250/492.2

2 376/105

2 438/514
Cross-Reference Classifications
4 250/398
3 250/397
3 250/492.2
2 250/281
2 250/305
2 250/423R
2 250/492 21
                     250/423R
250/492.21
313/361.1
313/362.1
315/111.41
315/505
376/120
430/599
                       430/600
                       510/276
Combined Classifications
10 250/492.21
5 250/492.2
4 250/397
4 250/398
3 250/423R
2 204/252
2 204/296
2 250/281
2 250/305
2 250/442.11
2 313/359.1
                    250/442.11
313/359.1
313/361.1
313/362.1
315/111.41
315/505
376/105
376/105
376/120
430/567
430/599
430/600
438/514
438/766
                      438/766
510/224
                       510/276
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## 10696782\_CLSTITLES.txt

Titles of Most Frequently Occurring Classifications of Patents Returned From A Search of 10696782 on February 15, 2005

```
(8 OR, 2 XR)
250 : RADIANT ENERGY
10 250/492.21
          Class
          250/492.1
                          IRRADIATION OF OBJECTS OR MATERIAL
                          .Irradiation of semiconductor devices
          250/492.2
          250/492.21
                          ..Ion bombardment
          192.2 (2 OR, 3 XR)
Class 250: RADIANT ENERGY
250/492.1 IRRADIATION 05
 5 250/492.2
                          IRRADIATION OF OBJECTS OR MATERIAL .Irradiation of semiconductor devices
          250/492.2
          97 (1 OR, 3 XR)
Class 250: RADIANT ENERGY
          250/396R
                          WITH CHARGED PARTICLE BEAM DEFLECTION OR
                              FOCUSSING
          250/397
                          .With detector
                    (0 \text{ OR}, 4 \text{ XR})
          Class 250: RADIANT ENERGY
          250/396R
                          WITH CHARGED PARTICLE BEAM DEFLECTION OR
                               FOCUSSING
          250/398
                          .With target means
          23R (1 OR, 2 XR)
Class 250: RADIANT ENERGY
   250/423R`
          250/423R
                          ION GENERATION
                   (1 OR, 1 XR)
204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
   204/252
          Class
          204/193
                          APPARATUS
          204/194
                          .Electrolytic
                          ..Cells
          204/242
          204/252
                          ...Diaphragm type
   204/296
                     (1 OR, 1 XR)
          Class
                 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
          204/193
204/194
                          APPARATUS
                          .Electrolytic
          204/279
                          ..Elements
                          ...Diaphragms
          204/295
          204/296
                          ....Organic
                   (0 OR, 2 XR)
250 : RADIANT ENERGY
 2 250/281
          Class
          250/281
                          IONIC SEPARATION OR ANALYSIS
          05 (0 OR, 2 XR)
Class 250: RADIANT ENERGY
   250/305
          250/305
                          ELECTRON ENERGY ANALYSIS
                   (1 OR, 1 XR)
250 : RADIANT ENERGY
 2 250/442.11
          Class
                          INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED
          250/306
                                PARTICLES
          250/440.11
                          .Analyte supports
          250/442.11
                          .. With object moving or positioning means
                   (1 OR, 1 XR)
313 : ELECTRIC LAMP AND DISCHARGE DEVICES
   313/359.1
          Class
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10696782_CLSTITLES.txt
         313/359.1
                          WITH POSITIVE OR NEGATIVE ION ACCELERATION
  313/361.1
                    (0 \text{ or, } 2 \text{ xr})
                   313 : ELECTRIC LAMP AND DISCHARGE DEVICES
         Class
         313/359.1
                          WITH POSITIVE OR NEGATIVE ION ACCELERATION .Means for deflecting or focusing
         313/361.1
                   (0 OR, 2 XR)
2 313/362.1
                   313 : ELECTRIC LAMP AND DISCHARGE DEVICES
         Class
         313/359.1
                          WITH POSITIVE OR NEGATIVE ION ACCELERATION .Supplying ionizable material (e.g., gas or
         313/362.1
                              vapor)
  315/111.41
                    (0 \text{ OR}, 2 \text{ XR})
         Class
                          ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
         315/111.01
                          DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
                                SUPPLY TO THE DISCHARGE SPACE
         315/111.21
                          .Plasma generating
         315/111.41
                          ..With magnetic field
2 315/111.81
                    (1 \text{ OR}, 1 \text{ XR})
                   315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
         Class
         315/111.01
                          DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
                          SUPPLY TO THE DISCHARGE SPACE .Electron or ion source
         315/111.81
2 315/505
                    (0 \text{ OR}, 2 \text{ XR})
         Class
                   315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
         315/500
315/501
                          HIGH ENERGY PARTICLE ACCELERATOR TUBE .Magnetic field acceleration means
         315/505
                          ..Linear accelerator (Linac)
2 376/105
                    (2 OR, 0 XR)
                   376 :
         Class
                           INDUCED NUCLEAR REACTIONS:
                                                            PROCESSES,
                            SYSTEMS, AND ELEMENTS
                          NUCLEAR FUSION
         376/100
                          .Inertial confinement (e.g., nuclear explosive)
         376/102
                          .. Particle beam irradiation (excluding photons)
         376/105
                    (0 \text{ OR}, 2 \text{ XR})
2 376/120
         Class
                   376 : INDUCED NUCLEAR REACTIONS: PROCESSES,
                            SYSTEMS, AND ELEMENTS
         376/100
376/120
                          NUCLEAR FUSION
                          .Including bunched particle beam
2 430/567
                    (1 \text{ OR}, 1 \text{ XR})
                           RADIATION IMAGERY CHEMISTRY: PROCESS,
         Class
                   430 :
                          COMPOSITION, OR PRODUCT THEREOF RADIATION SENSITIVE PRODUCT
         430/495.1
430/564
430/567
                          .Silver compound sensitizer containing
                          ..Silver compound having specified crystal
                             form, habit, particle size or particle size distribution
2 430/599
                    (0 \text{ or, } 2 \text{ xr})
                           RADIATION IMAGERY CHEMISTRY: PROCESS,
         Class
                  430 :
                            COMPOSITION, OR PRODUCT THEREOF
         430/495.1
                          RADIATION SENSITIVE PRODUCT
         430/564
                          .Silver compound sensitizer containing
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10696782_CLSTITLES.txt
           430/599
                            .. Hypersensitizing or latensifying ingredient
                                containing
  2 430/600
                      (0 \text{ OR}, 2 \text{ XR})
                            RADIATION IMAGERY CHEMISTRY: PROCESS,
           Class
                              COMPOSITION, OR PRODUCT THEREOF
           430/495.1
                            RADIATION SENSITIVE PRODUCT
           430/564
                            .Silver compound sensitizer containing
           430/599
                            ... Hypersensitizing or latensifying ingredient
                                 .
containing
                            ...Heterocyclic N, O, S, Se, or Te compound
           430/600
                                containing
  2 438/514
                      (2 OR, 0 XR)
           Class
                            SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
           438/510
                            INTRODUCTION OF CONDUCTIVITY MODIFYING DOPANT
                                 INTO SEMICONDUCTIVE MATERIAL
           438/514
                            .Ion implantation of dopant into semiconductor
                                region
    438/766
                      (1 \text{ OR}, 1 \text{ XR})
           Class
                     438 :
                             SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
           438/758
                            COATING OF SUBSTRATE CONTAINING SEMICONDUCTOR
                                  REGION OR OF SEMICONDUCTOR SUBSTRATE
           438/765
                            .By reaction with substrate
                            ..Implantation of ion (e.g., to form ion amorphousized region prior to selective oxidation,
           438/766
reacting
                               with substrate to form insulative region, etc.)
  2 510/224
                      (1 OR, 1 XR)
                             CLEANING COMPOSITIONS FOR SOLID SURFACES
           Class
                     510:
                              AUXILIARY COMPOSITIONS THEREFOR, OR PROCESSES
                                                                                       0F
                              PREPARING THE COMPOSITIONS
           510/108
                            CLEANING COMPOSITIONS OR PROCESSES OF PREPARING
                                    (E.G., SODIUM BISULFATE COMPONENT, ETC.)
                            .For cleaning a specific substrate or removing
           510/109
                                   a specific contaminant (e.g., for smoker's pipe, etc.)
                            ... For equipment used in processing, handling,
           510/218
                                  storing, or serving edible product (e.g., dairy or
brewery
                                  equipment, household utensils, etc.)
           510/220
                            ...For use in automatic dishwasher
           510/224
                            ....Solid, shaped article (e.g., tablet,
                                briquette, pellet, etc.)
  2 510/276
                      (0 \text{ or}, 2 \text{ xr})
           Class
                             CLEANING COMPOSITIONS FOR SOLID SURFACES,
                              AUXILIARY COMPOSITIONS THEREFOR, OR PROCESSES
                                                                                       OF
                              PREPARING THE COMPOSITIONS
                            CLEANING COMPOSITIONS OR PROCESSES OF PREPARING

(E.G., SODIUM BISULFATE COMPONENT, ETC.)

.For cleaning a specific substrate or removing

a specific contaminant (e.g., for smoker's pipe, etc.)

..For textile material (e.g., laundry
           510/108
           510/109
           510/276
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detergent, etc.)